

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE  
(Case No. 213.002-D1-US)

In the Application of: **Ye et al.**

Serial No: **10/646,313**

Filed: **August 22, 2003**

Title: **SYSTEM AND METHOD FOR LITHOGRAPHY  
PROCESS MONITORING AND CONTROL**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

) Group Art Unit:

) Before Examiner

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on January 9, 2004

Date  
Michelle Sites  
(person signing this certificate)

Michelle Sites  
Signature

**FIRST INFORMATION DISCLOSURE STATEMENT**

Dear Sir:

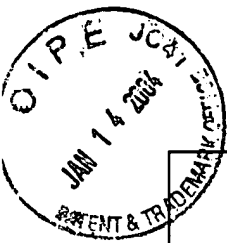
Submitted herewith are eight (8) sheets of a modified Form PTO-1449. All of the documents listed on the modified Form PTO-1449 were provided or cited in the parent application of the above-captioned application. Accordingly, the documents are not enclosed herewith. (See 37 C.F.R. §1.98(d) and MPEP 609). Should the Examiner desire an additional copy of the documents, kindly contact the undersigned.

It is respectfully requested that the Examiner make his/her consideration of these references formally of record with the initial Office Action.

Respectfully submitted,

Date: January 9, 2004

Neil A. Steinberg  
Reg. No. 34,735  
650-968-8079



PTO-1449 (Modified)  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. <b>213.002-D1-US</b>	SERIAL NUMBER <b>10/646,313</b>
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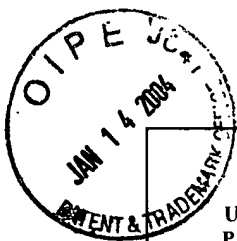
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	EP 0 628 806	4/1994	European			

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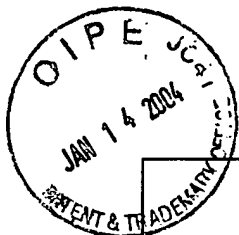
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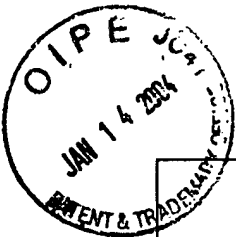
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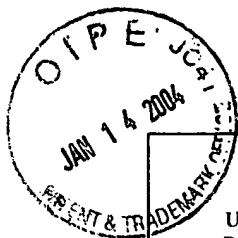
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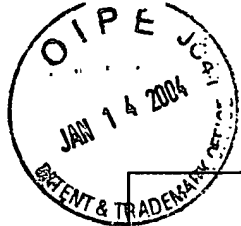
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